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**Complete if Known**

Application Number

10/674.568

Filing Date

**September 29, 2003**

**First Named Inventor**

Davis, et al.

**Art Unit**

**Examiner Name**

Attorney Docket Number

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[illegible][illegible]

**Examiner  
Signature**

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Date Considered

9-16-05

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U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)					Docket No. 6716/ETCH/SILICON/JB		Serial No. 10/674,568	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>					Applicant Davis, et al.		Confirmation No.:	
(Use several sheets if necessary)					Filing Date September 29, 2003		Group	
Examiner								
<b>U.S. Patent Documents</b>								
*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate	
N	A1	4,767,496	08/30/1988	Hieber	156	627		
N	A2	5,798,529	08/25/1998	Wagner	250	492.2		
N	A3	5,926,690	07/20/1999	Toprac et al.	438	17		
N	A4	5,948,203	09/07/1999	Wang	156	345		
N	A5	6,004,706	12/21/1999	Ausschnitt et al.	430	30		
N	A6	6,027,842	02/22/2000	Ausschnitt et al.	430	30		
N	A7	6,161,054	12/12/2000	Rosenthal et al.	700	121		
N	A8	6,245,581	06/12/2001	Bonser et al.	438	8		
N	A9	6,424,417	07/23/2002	Cohen et al.	356	388		
N	A10	6,486,492	11/26/2002	Su	257	48		
N	A11	2002/0171828	11/21/2002	Cohen et al.	356	328	07/01/2002	
<b>Foreign Patent Documents</b>								
*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1						<input type="checkbox"/>	<input type="checkbox"/>
	B2						<input type="checkbox"/>	<input type="checkbox"/>
<b>OTHER ART</b>								
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.						
N	C1	Lee, et al., "Analysis of Reflectometry and Ellipsometry Data from Patterned Structures," Characterization and Metrology for UCSI Technology: 1998 International Conference, Seiler, et al., eds., pg 331-335						
N	C2	Raymond, "Angle-resolved scatterometry for semiconductor manufacture," Microlithography World, Winter 2000.						
N	C3	Toprac, A., "AMD's Advanced Process Control of Ply-Gate Critical Dimension," Proc. SPIE Vol 3882, pg 62-65, Sept, 1999.						
N	C4	Yang, et al., "Line-profile and Critical Dimension Measurements Using a Normal Incidence Optical Metrology System," Proceedings of SPIE Vol. 4689, March 2002,						
Examiner <i>R</i>					Date Considered 9-16-05			
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